

Amendments to the Specification

Please replace the paragraph on page 1, beginning on line 4, with the following amended paragraph:

The present invention relates to an end point detector suitable for manufacture of semiconductor devices and more particularly to an ~~[[EDP]]~~ EPD (end point detector) suitable for use in plasma dry etching equipment as one component of semiconductor manufacturing equipment.

Please replace the paragraph on page 12, beginning on line 20, with the following amended paragraph:

The sensor collector barrel 51 has the same connector as has been discussed in the first or second embodiment. The barrel body that extends from the connector increases in diameter as one goes from the connector as the proximal end toward the distal end so that a taper angle ~~[[1]]~~ θ_1 is formed.

Please replace the abstract with the following new abstract:

An end point detector for detecting the monitor light to control the operation of an etching process by the etching equipment based on changes in the monitor light supplied from plasma etching equipment. The end point detector ~~comprises~~ includes a sensor body for detecting the monitor light and a collector barrel for guiding the monitor light from the etching equipment to the sensor body, wherein the collector barrel is detachable from the sensor body.